

ABSTRACT OF THE DISCLOSURE

A photoresist supply apparatus is provided. The photoresist supply apparatus includes a lower photoresist sensor and an upper photoresist sensor respectively installed near the

5 bottom and the top of a trap tank to detect a photoresist in the trap tank. A drain line is connected to an upper side of the trap tank to release air. A photoresist-blocking valve is installed at the drain line, the photoresist-blocking valve structured to be opened to release air or closed to prevent photoresist loss according to signals detected by the lower photoresist sensor and the upper photoresist sensor. While the photoresist is supplied into the trap tank,

10 the photoresist-blocking valve is opened to release air. After the photoresist supply into the trap tank is completed, the photoresist-blocking valve is closed to prevent the loss of a large amount of the photoresist through the drain line.